



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: $>90\%CA$
3. SURFACE QUALITY(S1,S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda/4@633\text{nm}$ (SUBSTRATE)
5. PARALLELISM(S1,S2): $<3\text{ arcmin}$
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 FILTERING(S1): $T_{\text{avg}}>90\%$, $T_{\text{abs}}>85\%@750-1100\text{nm}$, 45°AOI
 $R_{\text{avg}}>95\%$, $R_{\text{abs}}>90\%@1260-1700\text{nm}$, 45°AOI
 AR COATING(S2): $R_{\text{abs}}<2\%@750-1100\text{nm}$, 45°AOI

DRAWING PROJECTION			LBTEK			
	NAME	DATE	DM20-1180SP			
DRAWN	LZHOU	JUL./30th/24	SHORTWAVE DICHOIC MIRROR $\phi 50.8\text{mm} \times 5\text{mm}$, 1180 nm			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	22.3 g	1:1	A